

PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants : Pietro Erratico et al.  
Filed : November 12, 2003  
For : PROCESS FOR FORMING A BURIED CAVITY IN A  
SEMICONDUCTOR MATERIAL WAFER AND A  
BURIED CAVITY

Art Unit : 1765  
Docket No. : 854063.618D1  
Date : November 12, 2003

Mail Stop Patent Application  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

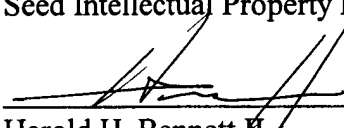
Commissioner for Patents:

In accordance with 37 C.F.R. §§ 1.56 and 1.97 through 1.98, applicants wish to make known to the Patent and Trademark Office the 17 references set forth on the attached Form PTO-1449. This application relies, under 35 U.S.C. § 120, on the earlier filing date of prior Application No. 09/797,206, filed February 27, 2001. The references listed on the attached Form PTO-1449 were submitted to and/or cited by the Patent and Trademark Office in this prior application and, therefore, are not required to be provided in this application. If the Examiner wishes, copies will be provided upon request. As to any reference supplied, applicants do not admit that it is "prior art" under 35 U.S.C. §§ 102 or 103, and specifically reserve the right to traverse or antedate any such reference, as by a showing under 37 C.F.R. § 1.131 or other method. Although the aforesaid references are made known to the Patent and Trademark Office in compliance with applicants' duty to disclose all information they are aware of which is believed relevant to the examination of the above-identified application, applicants believe that their invention is patentable.

Please acknowledge receipt of this Information Disclosure Statement and kindly make the cited references of record in the above-identified application.

Applicants believe this Information Disclosure Statement has been timely filed, however, the Director is authorized to charge any fee due by way of this Information Disclosure Statement to our Deposit Account No. 19-1090.

Respectfully submitted,  
Seed Intellectual Property Law Group PLLC



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Enclosures:

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Form PTO-1449

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FORM PTO-1449 (REV. 7-80)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. <b>854063.618D1</b>	APPLICATION NO.		
<b>INFORMATION DISCLOSURE STATEMENT</b> <i>(Use several sheets if necessary)</i>				APPLICANTS <b>Pietro Erratico et al.</b>			
				FILING DATE <b>November 12, 2003</b>		GROUP ART UNIT	
<b>U.S. PATENT DOCUMENTS</b>							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	3,969,168	07/13/76	Kuhn	156	17	
	AB	4,993,143	02/19/91	Sidner	29	621.1	
	AC	5,773,870	06/30/98	Su et al.	257	531	
	AD	6,001,666	12/14/99	Diem et al.	438	52	
	AE	6,015,761	01/18/00	Merry et al.	438	727	
<b>FOREIGN PATENT DOCUMENTS</b>							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION		
					YES	NO	
	AF	JP62076783	04/08/87	Japan (Abstract Only)			
	AG	JP62076784	04/08/87	Japan (Abstract Only)			
	AH	WO9417558	08/04/94	PCT			
	AI	0 658 927 A	06/21/95	Europe (+ Abstract)			
	AJ	960177-7 A	11/10/97	Sweden (+ Abstract)			
	AK	196 21 349 A	12/04/97	Germany (+ Abstract)			
	AL	1 043 770 A1	10/11/00	EP			
	AM	1 130 631 A1	09/05/01	EP			
<b>OTHER PRIOR ART</b> <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							
	AN	Schubert, "Method of Making Separate Regions of Various Average Depths with One Anisotropic Etch," Research Disclosure, No. 316, Emsworth, GB, August, 1990, pp. 688-689.					
	AO	Zou et al., "Single-Chip Fabrication of Integrated Fluid System (IFS), <i>IEEE Workshop on Micro Electro Mechanical Systems</i> , New York, NY: IEEE, 25 January 1998, pp 448-453					
	AP	"Method of Making Separate Regions of Various Average Depths with one Anisotropic Etch," <i>Research Disclosure, GB, Industrial Opportunities Ltd., Havant, No. 316</i> , August 1990					
	AQ	Sugiyama et al., "Micro-Diaphragm Pressure Sensor," <i>1986 IEEE</i> , 8.3, 184-IEDM, pp 184-187.					
EXAMINER				DATE CONSIDERED			
<b>* EXAMINER:</b> Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).							